

AMENDMENTS TO THE CLAIMS

This listing of claims replaces all prior versions, and listings, of claims in the application.

Claim 1 (Cancelled).

2. (Currently Amended) The ~~photomask~~pair of photomasks according to claim ~~1~~21, wherein the line width of each of said line patterns is at least λ/NA , where λ is the wavelength of the exposing light of an exposing apparatus used for transferring the patterns, and NA is the numerical aperture of a projection lens of the exposing apparatus.

3. (Currently Amended) The ~~photomask~~pair of photomasks according to claim ~~1~~21, wherein said linear portions of said light-shielding material of said plurality of line patterns of said central pattern portions are at least 10 μm in length.

4. (Currently Amended) The ~~photomask~~pair of photomasks according to claim ~~1~~21, wherein the number of said linear portions of said plurality of line patterns of each of said central pattern ~~portion~~portions is 9.

Claim 5 (Cancelled).

6. (Currently Amended) The ~~photomask~~pair of photomasks according to claim ~~1~~21, wherein

said open portion of one of said photomasks has a width equal to or larger than a threshold value, ~~wherein and~~

the threshold value is the width of said open portion when the line width of a transferred pattern corresponding to said plurality of line patterns in said central portion becomes constant, despite widening of said open portion.

Claims 7-20 (Cancelled).

21. (Currently Amended) A pair of photomasks for measuring ~~flair~~flare rate, each photomask comprising:

a substrate composed of a material transmitting exposing light; and

a pattern on said substrate of a light-shielding material that does not transmit the exposing light, wherein

each of said patterns includes

a central pattern portion having a plurality of line patterns on a central portion of said substrate,

an open portion where no light-shielding material is located and surrounding said central pattern portion, and

a peripheral pattern portion located on and proximate a peripheral portion of said substrate, surrounding the open portion and having a plurality of line patterns,

said central pattern portions of said pair of photomasks have identical configurations,

the open portions of said pair of photomasks are different in size from each other, and

said peripheral pattern portions of said pair of photomasks are different in size from each other.